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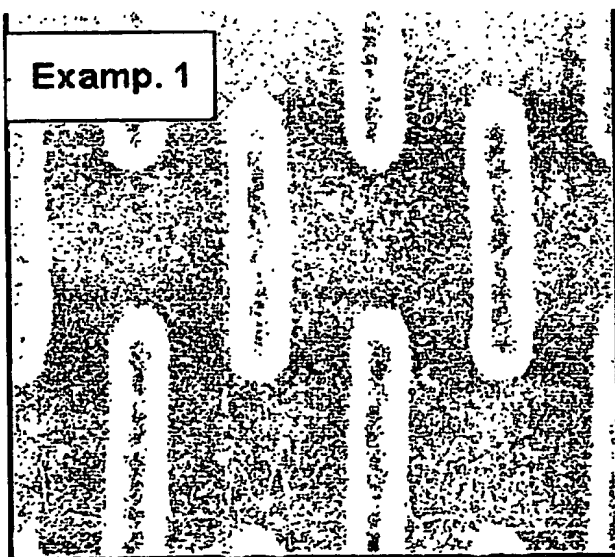
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(54) Title: ORGANIC BOTTOM ANTI-REFLECTIVE COMPOSITION AND PATTERNING METHOD USING THE SAME

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(57) Abstract: The present invention relates to an organic anti-reflective composition and a patterning method using the same, more particularly to an organic anti-reflective composition comprising a crosslinking agent, a light absorbing agent, a thermal acid generator, an organic solvent and an adhesivity enhancer, and a patterning method using the same. The organic anti-reflective composition of the present invention can solve the standing wave effect due to change in optical properties and resist thickness of the bottom film on the wafer, prevent change of critical dimension (CD) due to scattered reflection, and prevent pattern collapse of photosensitizer on top of the organic anti-reflective film, and thus can form stable 64M, 256M, 512M, 1G, 4G and 16G DRAM ultrafine pattern and of improving product yield.